



OPTOFLUX

MSP1232

Training Syllabus

| Task | Day |
|-----------------------------------------------------------------|-----|
| System Overview | |
| Describe the system & process (1h) | 1 |
| Explain the components of the process module (1h) | 1 |
| Describe the vacuum system (1h) | 1 |
| Describe the system facilities (1h) | 1 |
| Safety | |
| Read chapter "Safety" of MSP Operating Instructions (1) | 1 |
| GUI Software | |
| Explain the design of the system control hardware (0.5h) | 1 |
| Login/logout KHAN GUI, select the operating mode (0.5h) | 1 |
| Describe the KHAN screens accessible in manufacturing mode (2h) | 1 |
| Demonstrate use of the online help (0.5h) | 1 |

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| Production Start | |
| Check the prerequisites for production start (0.5h) | 2 |
| Open and close the process chamber (0.5h) | 2 |
| Reload the substrate carrier (0.5h) | 2 |
| Replace the GSM monitor glass (0.5h) | 2 |
| Run a process (0.5h) | 2 |
| Maintenance | |
| Execute the process chamber maintenance (1h) | 2 |
| Execute the cathode maintenance (1h) | 2 |
| Execute the plasma source maintenance (1h) | 2 |
| Process training | |
| Describe the principle of reactive sputtering (1h) | 3 |
| Explain function and integration of Plasma Emission Monitor (1h) | 3 |
| Create a KHAN recipe for a 2 layer deposition (2h) | 3 |
| Explain the GSM system (3h) | 3 |
| Explain target material specific process parameters (2h) | 3 |
| Use the "Strategy Generator" to create a new recipe (4h) | 4 |
| Optimize film thickness uniformity by using "Uni Tune" (4h) | 4 |
| Reserve | |
| Various | 5 |
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